



**AMENDMENTS TO THE SPECIFICATION**

**Amend the specification prior to the first paragraph by deleting the following:**

**Applicant:**

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Our ref.: P 43346 DE \_\_\_\_\_ 18 November 2003 Mu/re

**Amend the first paragraph of the specification as follows:**

This is a continuation-in-part application ~~relating to US Patent of pending~~  
~~prior~~ Application with serial No. 10/151,867 and publication number US 002/0176166 A1, which  
~~was filed on 22-May 22, 2002, of Karl-Heinz SCHUSTER entitled POLARIZER AND~~  
MICROLITHOGRAPHY PROJECTION SYSTEM WITH A POLARIZER, and which, in turn,  
claims priority ~~over the~~ from German Patent Application No. ~~DE-101 24 803.2, filed on dated~~  
22-May 22, 2001.

**Amend the seventeenth paragraph, on page 8 of the specification, as follows:**

One variant is distinguished in that the main crystallographic axes of the retardation elements are aligned in different directions that are perpendicular to the optical axis of the retardation arrangement. For embodiments which are designed for substantially perpendicular incidence of radiation (incidence of radiation substantially parallel to the optical axis of the retardation arrangement), the birefringent transmission element can be constructed substantially as shown in ~~DE 195 35 292~~ DE 195 35 392. The disclosure content of ~~DE 195 35 292~~ DE 195 35 392 is incorporated into the content of this description by reference. However, since a two-fold

passage of the radiation through the transparent birefringent material occurs in the case of reflective retardation arrangements of the type described here, the axial thickness of the retardation elements can be reduced, for example halved, by comparison with the embodiments shown there. Higher order retardation arrangements (for example with phase retardations of more than one working wavelength) are likewise possible and can be correspondingly thicker.